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MAY 12 2003

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Ito, et al.

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Group Art Unit: 2881

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Serial No.: 09/830,631

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Examiner: K.T. Nguyen

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Confirmation No.: 1816

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Filed: April 30, 2001

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For: Ion Implantation Apparatus

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Commissioner for Patents
Alexandria, VA 22313-1450

Dear Sir:

CERTIFICATE OF MAILING

37 CFR 1.8

I hereby certify that this correspondence is being deposited on
5/7/03 with the United States Postal Service
as First Class Mail in an envelope addressed to:
Commissioner for Patents, P.O. Box 1450 Alexandria, VA
22313-1450.

5/7/03K.T. Nguyen

Date

Signature

**RESPONSE TO OFFICE ACTION DATED JANUARY 8, 2003
AND PROPOSED DRAWING AMENDMENT**

In response to the Office Action dated January 8, 2003, having a shortened statutory period for response extended one month to expire on May 8, 2003, please enter this response and reconsider the claims pending in the application for reasons discussed below. Although Applicants believe that no fee is due in connection with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/SOEI/0037/KMT, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

IN THE SPECIFICATION:

Please insert the following paragraph after page 5, line 26:

Fig. 6 is an alternative view of a shield section that replaces the shield section in Fig. 4.

Please replace the paragraph on page 19, lines 16-25 with the following paragraph:

The shield section 84 of this type can be a flat-plate-shape member which has the shield surface 84a at one end, the shield surface 84a making an acute angle with the wall surface 24d of the guide tube, and which extends in the direction of the ion beam 64 on the internal wall 24d as shown in Fig. 4. Alternatively, as shown in Fig. 6, a shield section 100 may also be constructed of a flat plate 102 one surface of which forms the shield surface 102a and which extends at an acute angle from the wall surface 24d, and a frame member 104 supporting the flat plate.

IN THE DRAWINGS:

Applicants propose amending the drawings by adding Figure 6 (attached), which shows a shield section 100 having a flat plate 102 having a shield surface 102a and a frame member 104.

IN THE CLAIMS:

Please amend the claims as follows:

1. (Amended) An ion implantation apparatus comprising:
 - an ion source section for generating ions;
 - an ion implantation section for implanting said ions generated in said ion source section, in a substrate,
 - a charged particle generator for generating charged particles having a charge opposite to that of said ions, the charge particle generator including a filament coil and a plasma generating chamber housing the filament coil;
 - a beam guide section having an inlet aperture for accepting said ions from said ion source section, an outlet aperture for delivering said ions into said ion implantation section, a guide tube extending from said inlet aperture to said outlet aperture, and an